# Selective growth of single-walled carbon nanotubes by plasma enhanced chemical vapor deposition

プラズマCVDによる単層カーボンナノチューブの選択合成

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Atmospheric pressure radio-frequency discharge (APRFD) has advantage over vacuum-oriented plasma enhanced chemical vapor deposition (PECVD) in terms of single-walled carbon nanotube (SWCNT) growth. Plasma-generated  $C_2H_2$  is the main CNT growth precursor in PECVD. In the cathode sheath of APRFD, approximately 30% of the CH<sub>4</sub> (initial feedstock) was converted into  $C_2H_6$ ,  $C_2H_4$  and  $C_2H_2$ . A trace amount of  $C_2H_2$  enabled the synthesis of SWCNTs in the thermal CVD regime. Hydrogen is necessary to grow SWCNTs under non-thermal plasma environment because  $H_2$  suppresses formation of excess amount of  $C_2H_2$ ; however,  $H_2$  does not eliminate amorphous carbon even at  $H_2/C_2H_2$  ratios of 300. Atmospheric-pressure PECVD performed with a He/CH<sub>4</sub>/H<sub>2</sub> system is equivalent to  $C_2H_2$ -assisted thermal CVD without an etching gas. Depending on pressure, in other words  $C_2H_2$  content, SW and MWCNTs can be selectively synthesized.

# 1. Introduction

There were no reports on SWCNT synthesis in the PECVD regime by 2003 [1]. Tremendous effort has been made towards the control growth of desired CNTs using unique properties of reactive plasma, enabling SWCNTs under the low-pressure remote plasma CVD system [2]. However, due to limited supply of plasma-generated reactive species, SWCNT growth rate is unexpectedly low and dense SWCNT film is hardly synthesized. Exceptionally, microwave remote plasma CVD successfully grew millimeter-tall SWCNTs [3]. Atmospheric pressure enhanced CVD (AP-PECVD) plasma was originally highlighted because of its simplicity and flexibility over the process parameters. More recently, it is recognized as one of the promising technique to grow vertically aligned SWCNTs [4,5].

In PECVD, conversion of initial feedstock into acetylene ( $C_2H_2$ ) is the key to determining CNT morphology and to enhance overall growth rate. Main role of  $H_2$ , as supposed to be an etchant, is actually to suppress  $C_2H_2$  formation during plasma-induced decomposition of initial feedstock. Note  $C_2H_2$ -sensitized thermal CVD does not fully reproduce plasma-grown SWCNTs due to the presence of ions [5]. In this paper, we focus on the gas analysis to identify the key species responsible for SWCNT growth in the non-thermal plasma environment. The role of plasma-generated  $C_2H_2$  on CNT growth is highlighted as a major CNT growth precursor and selective growth of SW and MWCNTs are discussed.

# 2. Experimental

A capacitively coupled RF discharge (13.56 MHz) was generated between two parallel-plate metallic electrodes separated by 5 mm. The RF power was transmitted through the upper electrode (40 mm diameter) equipped with water-cooled sintered metallic mesh plate [6]. The sintered metal plate was manufactured from stainless steel powders with an average grain size of 100 µm.

A catalyst-coated substrate was located on the heated bottom electrode. A detailed catalyst preparation procedure is described in Refs. [4]. Briefly, an aluminum oxide thin film with estimated thickness 20 nm was initially coated on a silicon substrate ( $15 \times 15$  mm). The iron catalyst was dip-coated using an iron-acetate-containing ethanol solution. The dip-coated substrate was annealed in air at 400 °C for five minutes. The iron oxide was reduced by atmospheric pressure RF discharge in the He and H<sub>2</sub> mixtures ( $1500, 10 \text{ cm}^3 \text{min}^{-1}$ ). After a five-minute plasma treatment at 500 °C, the substrate temperature was elevated to 700 °C, and the flow rates of He, H<sub>2</sub> and CH<sub>4</sub> were adjusted for CNT growth.

## 3. Online gas analysis in the plasma sheath

The gas component in the cathode plasma sheath was analyzed qualitatively using a quadrupole mass spectrometer (QMS; Prisma, Pfeiffer Vacuum Technology). A thin metallic capillary tube (outer diameter, 450  $\mu$ m; inner diameter, 250  $\mu$ m) with an outer diameter one-half of the sheath thickness was

inserted into the sheath. The reacting gas was extracted directly for online gas analysis, and fragment peaks from m/e = 1 to 100 were recorded. A clear difference is observed between m/e = 25 and 30. Except for methane, the main hydrocarbon component is  $C_2H_6$ , although a trace amount of  $C_2H_2$  and  $C_2H_4$  are possible. Other fragment peaks related to higher hydrocarbons, such as propane (m/e < 44) and butane (m/e < 58), were not detected. For quantitatively gas analysis, the reacting gas was accumulated in a gas bag and then analyzed by gas chromatography (Shimadzu, GC-8A).

Figure 1 shows the CH<sub>4</sub> conversion and selectivity for the C<sub>2</sub> hydrocarbons at different conditions. At 100 kPa, the main product is  $C_2H_6$ that corresponds well with mass spectrometry analysis. In addition, 20% of the  $C_2H_4$  and a trace amount of C<sub>2</sub>H<sub>2</sub> were detected and the product selectivity is influenced by  $H_2$  content.  $C_2H_2$ content was approximately 70 ppm with H<sub>2</sub> dilution and 220 ppm without H<sub>2</sub>. C<sub>2</sub>H<sub>6</sub> selectivity is remarkably decreased at 20 kPa. C<sub>2</sub>H<sub>6</sub> is produced by a three-body recombination of  $CH_3$  ( $CH_3 + CH_3$ )  $+ M = C_2H_6 + M$ ). The overall reaction rate is pressure dependent, thus C2H6 formation is suppressed as the total pressure decreases. Correspondingly, the selectivity for  $C_2H_4$  and  $C_2H_2$ was increased at reduced pressures.



Figure 1 CH<sub>4</sub> conversion and selectivity for the C<sub>2</sub> hydrocarbon.  $\Box$  20 kPa, H<sub>2</sub> = 0;  $\blacksquare$  100 kPa, H<sub>2</sub> = 90 cm<sup>3</sup>min<sup>-1</sup>. He/ CH<sub>4</sub> = 3000/48 cm<sup>3</sup>min<sup>-1</sup> and 60 W.

#### 3. Pressure-dependent selective growth of CNTs

CNTs produced at different total pressure and fixed input power (60 W) were characterized by micro-Raman spectroscopy equipped with 514 nm excitation laser (Seki Technotron STR750 Laser Raman Spectrometer). Figure 2 shows pressuredependent change in the peak intensity ratio of G-band to D-band of Raman spectrum (hereafter the G/D ratio). The G/D ratio decreases as total pressure decreases, implying formation of defective graphite structure is enhanced in the reduced pressure. In other word, G/D ratio deteriorates as  $C_2H_2$  increases. TEM analysis clearly showed that MWCNTs were preferentially synthesized at reduced pressure. In addition to total pressure, the G/D ratio depends greatly on initial amount of catalyst metal [8]. There is an optimum value for the initial amount of catalyst precursor for SWCNT growth.



Figure 2 Pressure-dependent change in the G/D ratio of CNTs: He/CH<sub>4</sub>/H<sub>2</sub>, 3000/48/90 cm<sup>3</sup>min<sup>-1</sup>; 60 W; 700°C; 3 min synthesis; Fe catalyst,  $\bullet$  0.15 and  $\blacksquare$  0.05 wt%

#### **Concluding remarks**

Plasma-produced  $C_2H_2$  is the key component to grow CNTs. Atmospheric pressure RF discharge enabled SWCNTs because it suppressed  $C_2H_2$ formation. SWCNTs turned MWCNTs as total pressure decreased where  $C_2H_2$  content increased. Note that ions are unique in plasma process thus  $C_2H_2$ -assisited thermal CVD does not fully reproduce plasma grown CNTs.

### Acknowledgements

The project was supported by KAKENHI. T.N. expresses great thank to Prof. Shigeo Maruyama (Department of Mechanical Engineering, The University of Tokyo) for the catalyst preparation.

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